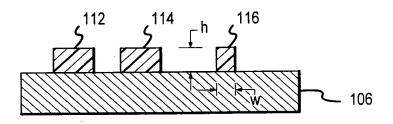
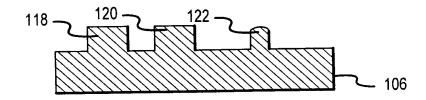


PRIOR ART FIG. 1a

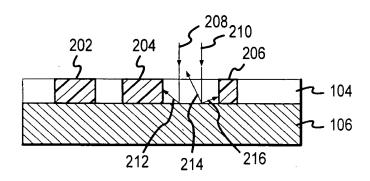


PRIOR ART FIG. 1b

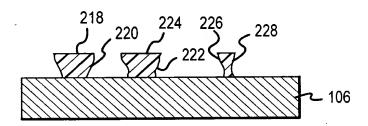


PRIOR ART FIG.1c

Title: Method & Apparatus For High-Resolution In-Plasma Etching of Inorganic and Metal Films Inventor(s): Hsia, et al. Dkt. No.: 50324-1141; Page 2 of 7

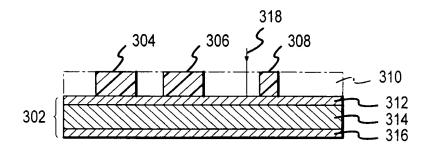


PRIOR ART FIG.2a



PRIOR ART FIG.2b

Title: Method & Apparatus For High-Resolution In-Situ Plasma Etching of Inorganic and Metal Films Inventor(s): Hsia, et al. Dkt. No.: 50324-1141; Page 3 of 7



**PRIOR ART** 

FIG.3a

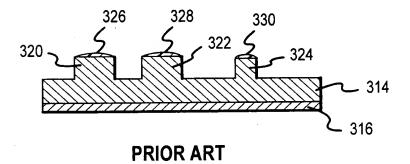


FIG.3b

Title: Method & Apparatus For High-Resolution In-Situ Plasma Etching of Inorganic and Metal Films Inventor(s): Hsia, et al. Dkt. No.: 50324-1141; Page 4 of 7

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FIG.4

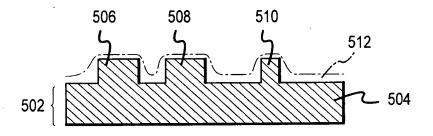


FIG.5

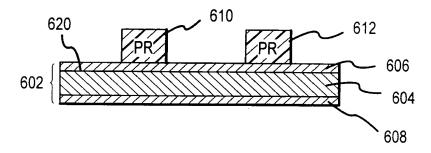


FIG.6a

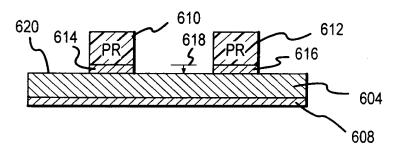


FIG.6b

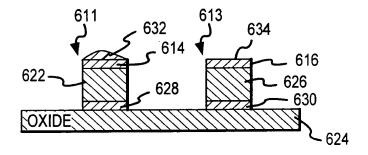


FIG.6c

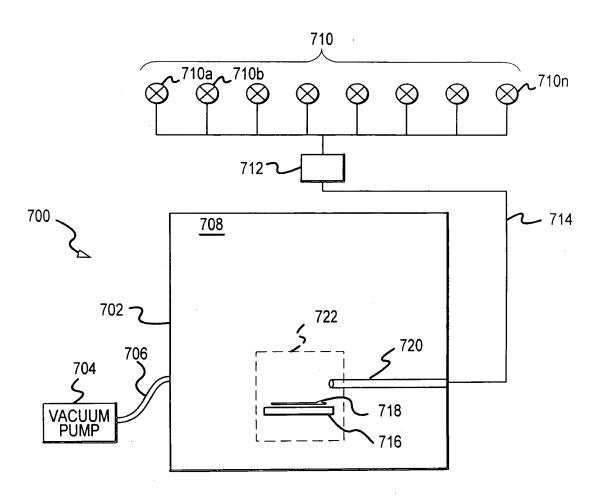


FIG.7

Title: Method & Apparatus For High-Resolution In-Situ Plasma Etching of Inorganic and Metal Fi Inventor(s): Hsia, et al. Dkt. No.: 50324-1141; Page 7 of 7

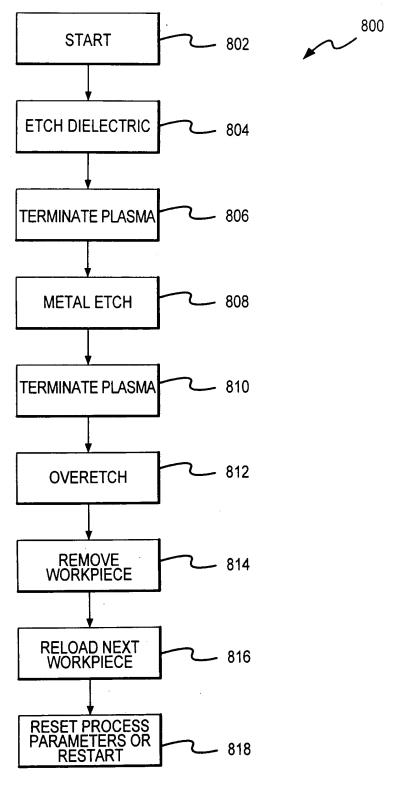


FIG.8